



500.37328CX1

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): YOKOGAWA, et al

Serial No.: 09/336,687 (CPA)

Filed: June 21, 1999

For: PLASMA PROCESSING SYSTEM AND METHOD

Group: 1763

Examiner: L. Alejandro

Handwritten: H13B
11/4/01
ML

RECEIVED
NOV 06 2001
TC 2800 MAIL ROOM

PRELIMINARY AMENDMENT

Commissioner for Patents
Washington, D.C. 20231

November 5, 2001

Sir:

The following preliminary amendments and remarks are respectfully submitted in connection with the above-identified CPA and is responsive to the Office Action dated July 3, 2001.

RECEIVED
NOV 06 2001
TC 11700

IN THE CLAIMS:

Please amend claim 33 as follows:

33. (twice amended) A plasma etching system in accordance with Claim 3, wherein:

the vacuum chamber includes an upper section made of an insulating material;

Handwritten: B'
[Signature]